

Characterization of Photo resist: SPR955-1.8

2. Exposed by GCA Autostep(new)

Conditions:

Focus offset: -7 -> 11 (inc:3)
Exposure time: 0.2s -> 0.8s (inc:0.1s)
Coating photo resist: 3000rpm (recipe 5)
Soft bake: 90s@95C
Post bake: 90s@110C

Exposure time →

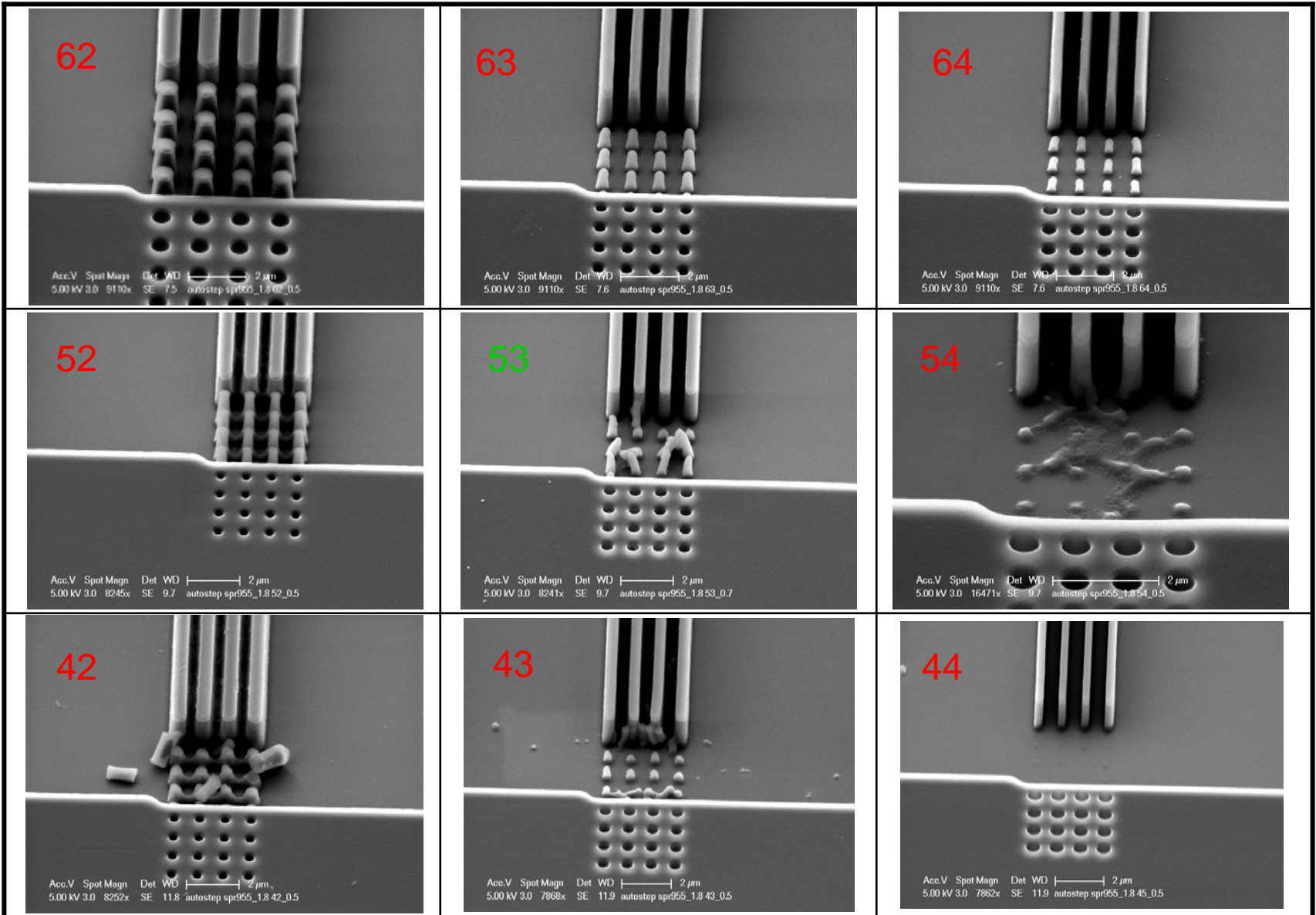
0.2s 0.3s 0.4s 0.5s 0.6s 0.7s 0.8s

Focus offset ↓

-7	71	72	73	74	75	76	77
-4	61	62	63	64	65	66	67
-1	51	52	53	54	55	56	57
2	41	42	43	44	45	46	47
5	31	32	33	34	35	36	37
8	21	22	23	24	25	26	27
11	11	12	13	14	15	16	17

2. GCA Autostep(new)

Best exposure results for 0.5 lines



2. GCA Autostep(new)

Best exposure results for 0.7 lines

